

LISTING OF THE CLAIMS

1– 17. (Cancelled)

18. (Previously Presented) A fabricating method of a transflective liquid crystal display device, comprising:

forming a gate line and a data line on a first substrate, the gate line and the data line crossing each other to define a pixel region having reflective and transmissive portions;

forming a thin film transistor connected to the gate line and the data line;

forming a first passivation layer on the thin film transistor, the first passivation layer having a plurality of protrusions in the reflective portion, wherein the plurality of protrusions are formed by patterning the first passivation layer, and wherein a top surface of the first passivation layer between the plurality of protrusions is substantially even;

forming an uneven reflective layer on the first passivation layer in the reflective portion that has unevenness at least in part due to the plurality of protrusions;

forming a pixel electrode on the first passivation layer;

providing a second substrate having a color filter layer, each color filter of the color filter layer having regions corresponding in dimension and arrangement to the reflective and transmissive portions of a pixel region and having at least one through hole in the reflective portion, the second substrate further comprising: an overcoat layer on the color filter layer, a surface of the overcoat layer having a recess portion in the transmissive region;

a common electrode on the surface of the overcoat layer; and

disposing the first substrate such that reflective and transmissive portions of the first substrate oppose the corresponding regions of the second substrate.

19. (Original) The method according to claim 18, further comprising forming a second passivation layer on the reflective layer and the pixel electrode on the second passivation layer.

20. (Original) The method according to claim 18, further comprising forming the reflective layer on the pixel electrode.

21. (Original) The method according to claim 18, wherein the reflective layer includes one of aluminum and aluminum alloy.

22. (Original) The method according to claim 18, further comprising forming an insulating layer of an inorganic material between the first passivation layer and the reflective layer.

23. (Original) The method according to claim 18, wherein the first passivation layer includes one of benzocyclobutene and acrylic resin.

24. (Previously Presented) The method according to claim 19, wherein the second passivation layer includes one of silicon oxide and silicon nitride.

25. (Previously Presented) The method according to claim 19, wherein the second passivation layer includes one of benzocyclobutene and acrylic resin.

26. (Original) The method according to claim 19, further comprising forming a contact hole through the first and second passivation layers and connecting the pixel electrode to the thin film transistor through the contact hole.

27. (Cancelled)

28. (Original) The method according to claim 18, further comprising substantially maintaining a thickness of the first passivation layer between the transmissive portion and a section of the reflective portion in which the transistor is absent.

29. (Original) The method according to claim 18, further comprising forming the first passivation layer in the transmissive portion.

30. (Original) The method according to claim 29, further comprising forming the first passivation layer in the transmissive portion such that no protrusions are formed in the transmissive portion.

31.- 35. (Cancelled)

36. (Previously Presented) The method according to claim 18, wherein the depth of the recess is dimensioned such that the distance between the common electrode in the transmissive portion and the first passivation layer is approximately twice the distance between the common electrode in the reflective portion and the first passivation layer.

37. (Cancelled)

38. (Previously Presented) The method according to claim 18, further comprising providing a liquid crystal layer in the transmissive and reflective portions and increasing a thickness of the liquid crystal layer in the transmissive portion compared with the thickness of the liquid crystal layer in the reflective portion without decreasing a thickness of any other layer on the substrate besides the reflective layer.